

[ABSTRACT]

PATTERNING METHOD AND PATTERNING APPARATUS

Disclosed is a patterning method, whereby a photocured pattern can be formed easily in a short time without detaching the photocured pattern (cured product) from a release layer. The method includes the steps of: (i) supplying a release material in a liquid state having a first specific gravity d_1 and a patterning material in a liquid state that has a second specific gravity d_2 smaller than the first specific gravity d_1 and phase-separates from the release material to a patterning tray including a bottom portion having a light-exposed surface to form a first liquid layer of the release material in contact with the bottom portion and form, on the first liquid layer, a second liquid layer of the patterning material in contact with the first liquid layer, and thereby forming a liquid film of the patterning material in a vicinity of an interface of the second liquid layer with the first liquid layer; and (ii) irradiating light to the liquid film via the first liquid layer to photocure the liquid film and form a pattern.

Fig 1